宋爽

2023年5月

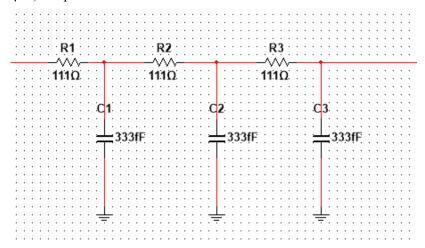
Exercise 7

7-1 Consider a 5 mm-long, 4 λ -wide metal2 wire in a 0.6 μ m process. The sheet resistance is 0.08 Ω/\Box and the capacitance is 0.2 fF/ μ m. Construct 3-segment L-model and 3-segment π -model for the wire. (Please present models and calculate delay).

Answer

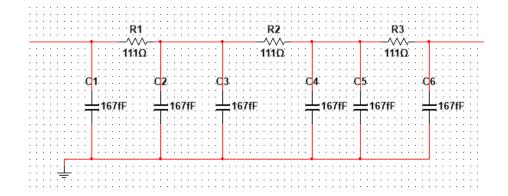
$$R = R_{\square} \frac{l}{w}$$

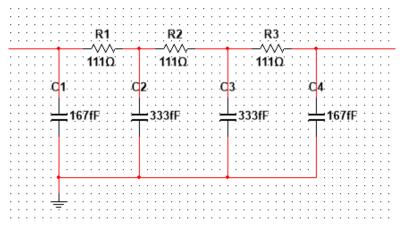
The wire width is $1.2\mu m$ so the wire is $5000\mu m/1.2\mu m = 4167$ squares in length So, the total resistance is $(0.08 \ \Omega/\text{ sq}) \times 4167 \ \text{sq}) = 333 \ \Omega$ The total capacitance is $(0.2 \ \text{fF}/\mu m) \times 5000\mu m) = 1 \ \text{pF}$



3-segment L-model

$$\tau = C_1 R_1 + C_2 (R_1 + R_2) + C_3 (R_1 + R_2 + R_3) = 2.22 \times 10^{-10} s$$





3-segment π -model

$$\tau = C_2 R_1 + C_3 (R_1 + R_2) + C_4 (R_1 + R_2 + R_3) = 1.67 \times 10^{-10} s$$

7-2 Assume an inverter is designed with a PMOS/NMOS ratio of 3.6 and the NMOS transistor is minimum size. (W = 0.375 μ m, L = 0.25 μ m, W/L = 1.5). VM=1.25V, VDD=2.5V. Please describe the voltage transfer characteristic and noise margins of CMOS inverter. (use V_{IL} , V_{IH} , NM_H , NM_L and g). The parameters shown in table 7.1.

Table7.1

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	V_{T0}	γ	$V_{ m DSAT}$	K	λ
	(V)	$(V^{1/2})$	(V)	$(\mu A/V^2)$	(V ⁻¹)
NMOS	0.7	0.45	0.83	134	0.1
PMOS	-0.8	-0.4	-1	-50	-0.2

Answer

$$I_D(V_M) = K_N (\frac{W}{L})_N (V_{GS} - V_{THN})^2 (1 + \lambda_n V_M) = 68.4 \times 10^{-6} A$$

$$g = \frac{-1}{I_D(V_M)} \times \frac{k_n \frac{W}{l_n} V_{DSATn} + k_p \frac{W}{l_p} V_{DSATp}}{\lambda_n - \lambda_p} = -24.93$$

$$V_{IH} = V_M - \frac{V_M}{g} = 1.3$$

$$V_{IL} = V_M + \frac{V_{DD} - V_M}{q} = 1.2$$

$$NM_H = V_{DD} - V_{IH} = 1.2$$
 $NM_L = V_{IL} = 1.2$